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MS-001

INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Boris Kobrin et al.  
Applicants

January 16, 2004  
Filing Date

Unknown  
Group

U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>AWK</u>	5,576,247	11/19/96	Yano et al.	437	225	
<u>AWK</u>	5,602,671	02/11/97	Hornbeck	359	224	
<u>AWK</u>	5,626,924	05/06/97	Ishikawa	427	759	
<u>AWK</u>	6,203,505	03/20/01	Jalisi et al.	600	585	
<u>AWK</u>	6,383,642	05/07/02	Le Bellac et al.	428	412	
<u>AWK</u>	6,576,489	06/10/03	Leung et al.	438	52	

U. S. PATENT APPLICATION DOCUMENTS

Examiner Initial	Document Number	Publication Date	Name	Class	Subclass	Filing Date
<u>AWK</u>	2001/0028924A1	10/11/01	Sherman	427	255.28	05/24/01
<u>AWK</u>	2002/0031618A1	03/14/02	Sherman	427	569	10/09/01
<u>AWK</u>	2002/0033229A1	03/21/02	Leboutz et al.	156	345	04/20/01

Examiner AWK Date Considered 6/26/05

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### U. S. PATENT APPLICATION DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date</u>
<u>AW</u>	2002/0076507A1	06/20/02	Chiang et al.	427	569	06/20/02
<u>AW</u>	2002/0146725A1	10/10/02	Mullen et al.	435	6	11/09/01
<u>AW</u>	2002/0195950A1	12/26/02	Mikhael et al.	315	111.21	08/26/02
<u>AW</u>	2003/0035904A1	02/20/03	Hsieh et al.	427	569	08/16/01
<u>AW</u>	2003/0040173A1	02/27/03	Fonash et al.	438	622	08/14/02
<u>AW</u>	2003/0138645A1	07/24/03	Gleason et al.	428	447	10/29/02

### FOREIGN PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
<u>AW</u>	JP 11116278	04/27/99	Hiromi et al.	C03C	17/28	
<u>AW</u>	WO 02/28956	04/11/02	Murphy et al.	C08L	1/28	

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- AW W. R. Ashurst et al., "Wafer Level Anti-Stiction Coatings With Superior Thermal Stability", Presentation at Hilton Head, South Caroline meeting, pp 1 - 4 (June 2002). Contact ashurbr@uclink4.berkeley.edu.
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- AW W. R. Ashurst et al., "Wafer level anti-stiction coatings for MEMS", Sensors and Actuators A, Elsevier Science B.V., Vol. 104, pp. 213 - 221 (2003).

<u>Examiner</u>	<u>Date Considered</u>
<u>AW</u>	<u>6/26/05</u>

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